

Synthesis and characterization of 2D Materials towards Energy Efficient Electronics

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Tunnel Transistors As a More Sensitive Electronic Switch





Tunnel Transistors As a More Sensitive Electronic Switch





Can we achieve 2D materials with 2D interface defect density <<10¹² states/cm²eV?



D_{it} Through Capacitance and AC Conductance Measurements



W. Zhu et. al, Nat. Comm. DOI: 10.1038/ncomms4087 (2014)

Device model:

$$Z = (Y_{itB} + Y_{itM} + i\omega C_s + i\omega C_j)^{-1} + (i\omega C_{ox})^{-1} + r_s \qquad C_{ms} = -\frac{1}{\omega * Im[Z]}$$



- C_s : the quantum capacitance, C_j : the parasitic capacitance, C_{ox} : the oxide capacitance, r_s : the series resistance
- Y_{itM} and Y_{itB} : admittance of the traps $(Y_{itB} = [\tau_{itB}/C_{itB} + 1/(i\omega C_{itB})]^{-1})$





D_{it} Through Capacitance and AC Conductance Measurements





D_{it} Through Capacitance and AC Conductance Measurements



$$D_{\rm n}(E) = \begin{cases} \alpha D_0 \exp\left[\frac{E - E_{\rm D}}{\varphi}\right] + D_{\rm itM}, & E_{\rm D} - \frac{1}{2}E_{\rm G} < E < E_{\rm D} \\ D_0 - (1 - \alpha)D_0 \exp\left[-\frac{E - E_{\rm D}}{\varphi'}\right] + D_{\rm itM}, & E > E_{\rm D} \end{cases}$$

 D_0 : 3.3 × 10¹⁴ eV⁻¹cm⁻² (the 2D density-of-states for MoS₂) φ : the characteristic energy width of the band tail φ ' is chosen so that the two piece-wise functions have continuous gradients at E_D

Best fit α =0.33 and φ = 100 meV. ₃

- band tail states follow an exponentially decaying behavior
- a significantly large energy width of 100 meV



W. Zhu et. al, **Nat. Comm.** DOI: 10.1038/ncomms4087 (2014)

Improving from previous results

- Understanding of the microscopic origin of these trap states is critical
 - for further improvement of the material's electronic properties
 - Contribution from the substrate, processing:
 - \circ hBN substrate vs. SiO2
 - \circ Transfer process
 - Intrinsic materials quality
 - $\,\circ\,$ Characterization /correlation
 - $\,\circ\,$ Improve on the synthesis process





Goal: High quality 2D materials with low defect densities

<u>Defect characterization</u>

>Various types of defects and characterization development

Contribution to defect states



• Defect traps states characterization

W. Zhou et. al, **Nano Letters** 13, 2615-2622, (2013)

- C-V and D_{it} measurement
- Correlation with device characteristics: mobility, contact resistance
- Correlation with optical characteristics?

MoS2 will be used as a model system Work in Progress!





Grain boundary defect characterization



 Photoluminescence mapping (Intensity, peak position): 440nm resolution



Z. Liu et. al, Nat. Comm 5, 5346 (2014)

• SNOM PL mapping: 110nm resolution



Y. Lee et. al, Nanoscale 7, 11909 (2015)





Phase-Modulated Optical Parametric Amplification Imaging

- EOM: modulates the relative optical phase between the two fields (1 MHz to a depth of 2π) according to a saw tooth waveform
- the two fields exchange intensity according to the phase modulation and the sample's nonlinear response
- Advantages over SHG:
 - Much easier
 - No need for single photon detector
 - Normal room lighting
 - Capture phase of the input signal in addition to its magnitude





Y. Gao et. al., manuscript in preparation





Collaboration with William Tisdale group in Chem E at MIT^{Center for Energy Efficient}

MoS₂ Grain Orientation

• Second harmonic generation (SHG) in monolayer MoS2



• pOPA signals in monolayer MoS2





 θ : orientation of monolayer MoS_2 triangle relative to the field polarizations





MoS₂ Grain Characterization



- Grains with mirror symmetry distinguished
- Better contrast and higher resolution

Y. Gao et. al., manuscript in preparation Collaboration with William Tisdale group in ChemE @MIT



MoS₂ Grain Characterization











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MoS₂ Grain Characterization



Electronics Science





- Various types of grain boundaries contribute to midgap states or even metallic conduction
- Need to avoid these via growth of much larger single crystalline domains

Y. Gao et. al., manuscript in preparation

Collaboration with William Tisdale group in ChemE @MIT



Moving forward: large single crystal grains in MoS₂

• single crystalline Sapphire growth substrate



D. Dumcenco et. al, ACS Nano 9, 4611-4620 (2015)

• Oxygen assisted CVD



Direction





W. Chen et. al, **JACS** 137, 15632 (2015)

Improvement on the synthesis and transfer



Time

Moving forward: Correlating optical with electrical characterizations

- C-V measurement and device characterizations on MoS2 with various PL characteristics
 - ➢ Superacid treated MoS₂
- Capacitance measurement through "vertical" devices instead of "lateral": (collaboration with Prof. Ray Ashoori group at MIT)



Optical characterizations with various shapes of MoS₂



PL Fitting for Exciton and Trion Transitions



6500

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С

b

a



Oxygen passivation and enhanced optical absorption of MoS₂

- Sulfur vacancy: one shallow localized state around VBM, two others midgap
- Oxygen passivation: shallow localized state -> a flat "molecular state" 0.015eV above VBM Triangular type I (convex similar)



Low-Contact- Resistance Monolayer MoS₂ Transistors



Improvement on the synthesis and transfer

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• Clean transfer avoiding polymer residue



30x30nm





Synthesis of other 2D materials



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VS₂ vs. MoS₂: similar structures, complementary properties



Mater.	Stable phase	periodicity	Layer distance	bandgap
MoS_2	2H	0.316 nm	0.61 nm	1.8 eV (1L)
VS ₂	1T	0.322 nm	0.58 nm	metal



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Multilayer "VS₂" flakes



Q. Ji et al. Nano Lett. 17, 4908 (2017)

 $2\text{VCl}_3(s) \rightarrow \text{VCl}_4(g) + \text{VCl}_2(s); \text{VCl}_4(g) + 2\text{H}_2(g) + 2\text{S}(g) \rightarrow \text{VS}_2(s) + 4\text{HCl}(g)$









Hii

Two step CVD growth for hetero-structure



"VS₂" is first grown/transferred, and MoS2 grows adjacent to "VS₂" flakes







Roughening of the "VS₂" regions









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"VS₂" electrical contacts



• Preliminary results indicate better contact with "VS₂"





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Thank you very much!



